

## UMF Equipment – UV Ozone Cleaner

### Novascan PSD UV Ozone System

UV Ozone Cleaners are widely used in industry, production and academics labs to UV clean semiconductor wafers, UV clean LCD surfaces during manufacturing, remove and strip photoresist, improve surface wettability, UV clean AFM probes / tips, UV Clean SEM & TEM samples, UV polymer activation, assembly / bonding of PDMS / glass microfluidic devices, UV clean glass and a host of other UV Ozone cleaning and oxidation applications.

Novascan UV Ozone System is highly effective for non-acidic, dry, non-destructive atomic cleaning and removal of organic contaminants using intense 185 nm and 254 nm ultraviolet light. In the presence of oxygen, the 185 line produces Ozone and while the 254 line excites organic molecules on the surface. This combination drives the rapid destruction and decimation of organic contaminants.

- Features:
- Substrate size: Up to square 8"
  - Ozone killer: Provided

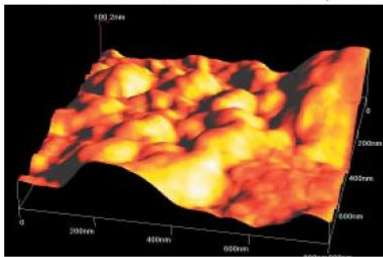
Please refer to supplier information page: <http://www.novascan.com/> for further details of the system.

For any inquiry, please contact Dr. Terence Wong (Tel: 3400 2075; Email: [tai-lun.wong@polyu.edu.hk](mailto:tai-lun.wong@polyu.edu.hk)).

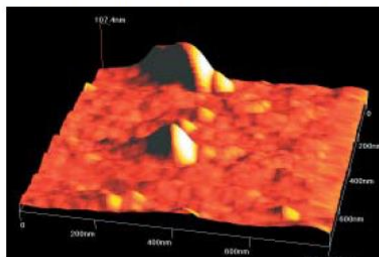


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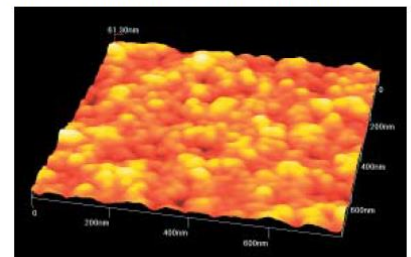
*Contaminated glass laboratory slide*



*Contaminated glass laboratory slide after 10 minutes of PSD treatment*



*Glass laboratory slide, decontaminated after 20 minutes of PSD treatment*



AFM study of contaminated glass slide surfaces before and after atomic cleaning with a Novascan UV Ozone Cleaner (Note that the data is autoscaled in the last AFM image to reveal the glass grain)  
[source: [http://www.novascan.com/products/uv\\_ozone\\_cleaners\\_silicon\\_glass\\_wafers.php](http://www.novascan.com/products/uv_ozone_cleaners_silicon_glass_wafers.php)]